REMARKS

Claims 1, 7, 8, and 10 are presently pending in the application.

Claim 9 has been canceled. Applicants respectfully submit that this amendment, in conjunction with the verified English translation being submitted herewith, will place the application in condition for allowance. Accordingly, entry of this amendment after final is deemed proper and respectfully requested.

In the Office Action, the Examiner has rejected claims 1 and 9-10 under 35 U.S.C. § 103(a) as being obvious over U.S. Patent No. 5,776,634 of Ohkuma et al. ("Ohkuma") in view of WO 02/48101 of Date et al. ("Date"), relying on U.S. Patent Application Publication No. 2004/0030158 of Date as an English equivalent, and further in view of U.S. Patent Application Publication No. 2005/0148679 of Chiu et al. ("Chiu"). Further, the Examiner has rejected claims 7 and 8 under 35 U.S.C. §103(a) as obvious over Ohkuma et al. in view of Date and Chiu and further in view of U.S. Patent Application Publication No. 2004/0137368 of Steinmann ("Steinmann"). Applicants respectfully traverse these rejections and the arguments in support thereof for the reasons set forth previously on the record, which Applicants rely upon in full, and for the additional reasons that follow, and respectfully request reconsideration and withdrawal of the rejections.

Rejection Under § 103(a) Based on Ohkuma in view of Date and Chiu

Regarding claims 1 and 9-10, the Examiner maintains that Ohkuma teaches a photosensitive recording medium composition containing a radical-polymerizable monomer, a cationic-polymerizable monomer, a radical polymerization initiator and a cationic-polymerization initiator. The cationic initiator may allegedly be represented by formula (I), which the Examiner contends is equivalent to claimed formula (I) when Ar is a phenyl group. The Examiner further argues that specific formula (II) of Ohkuma is equivalent to claimed formula (I) when M is a phosphorus atom. The Examiner acknowledges that Ohkuma does not teach the claimed purity of the cationic polymerization initiator or that the compound of formula (I) is the only compound dissolved or dispersed in a solvent.

However, as previously explained on the record, the Examiner takes the position that it would have been obvious for one skilled in the art at the time of the invention to use the sulfonium salts with a purity of 99% obtained in the process of Date as photocationic polymerization initiators in the composition of Ohkuma. The Examiner also concludes that it would have been obvious to apply the teachings of Chiu, allegedly teaching a composition in which the sulfonium salt is the only component in solution, to the Ohkuma/Date composition. Applicants respectfully traverse this rejection as follows.

Applicants note that the Chiu reference was filed on December 29, 2003, which is after Applicants' June 25, 2003 priority date, the filing date of the JP 2003-180470 priority document. Enclosed is a verified English translation of JP 2003-180470. It can be clearly seen that all of the pending claims are fully supported in the priority document at least in the claims and in paragraphs [0020], [0022], [0027], [0030], [0041], and in the Examples. Accordingly, because the present claims are fully supported in the priority document, Applicants are entitled to the June 25, 2003 priority date, and Chiu is not useable as an effective prior art reference. Removal of a secondary reference renders the rejection moot, and thus reconsideration and withdrawal of the § 103(a) rejection based on Ohkuma in view of Date and Chiu are respectfully requested.

Rejection Under § 103(a) Based on Ohkuma in view of Date, Chiu, and Steinmann

Regarding claims 7 and 8, the Examiner acknowledges that the proposed combination of Ohkuma, Date and Chiu does not teach that the composition comprises an oxetane compound and a polyalkylene ether compound as claimed. However, Steinmann allegedly teaches a radiation-curable composition useful for the production of three dimensional articles by stereolithography comprising at least one cationically polymerizing organic substance, at least one free-radical polymerizing organic substance, at least one cationic polymerization initiator, at least one free-radical polymerization initiator, at least one hydroxyl-functional compound, and at least one hydroxyl-functional oxetane compound. Accordingly, the Examiner concludes that it would have been obvious to one having ordinary skill in the art at the time of the invention to add at least one hydroxyl-functional compound, such as propylene glycols of various molecular weights, glycerine propoxylated polyether triol and polyethyleneglycols, and at least one hydroxyl-functional oxetane compound, as disclosed by Steinmann, to the composition of

Ohkuma/Date/Chiu in order to obtain a composition with exceptionally high photo speed, low viscosity, low humidity sensitivity, and high temperature resistance since such properties are taught by Steinmann. Applicants respectfully traverse this rejection as follows.

As explained above, Chiu is not effective prior art against the present application, and removal of a secondary reference renders the rejection moot. Accordingly, reconsideration and withdrawal of the §103(a) rejection based on Ohkuma in view of Date, Chiu, and Steinmann are respectfully requested

In view of the preceding Amendment and Remarks, it is respectfully submitted that the pending claims are patentably distinct from the prior art of record and in condition for allowance. A Notice of Allowance is respectfully requested.

Respectfully submitted,
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(Date)

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Enclosure: Verified English translation of JP 2003-180470